



B-1 1756  
EPW

843.41042X00

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): K. Hayano, et al.

Application No.: 10/025,457

Filing Date: December 26, 2001

Allowed: May 18, 2004

Fee Paid: August 18, 2004

For: METHOD OF MANUFACTURING PHOTOMASK AND METHOD OF  
MANUFACTURING SEMICONDUCTOR INTEGRATED CIRCUIT  
DEVICE

Art Unit: 1756

Examiner: S. Mohamedulla

**RESPONSE TO NOTICE OF DRAWING INCONSISTENCY  
WITH SPECIFICATION**

Mail Stop Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

October 8, 2004

Sir:

In response to the Notice Of Drawing Inconsistency With Specification mailed  
September 8, 2004, please amend the above-identified application as listed in the  
following, and as set forth on the following pages:

Amendments to the Specification; and

Remarks are included following the amendments.